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ss Mail No. EV 423 775 022 US Sheet I of I

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Modified) PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE STATEMENT BY APPLICANT Sheet I of I
ATTY. DOCKET NO.
1726/US/I
APPLICANT:
Patrick H. Wnek et al.
FILING DATE
GROUP

- 2004

(Use several sheets if necessary)

## **U.S. PATENT DOCUMENTS**

Herewith

EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
N	4,641,005	02/1987	Seiferth	219	10.55 E	<u> </u>
M	4,786,513	11/1988	Monforton et al.	426	107	
M	4,825,025	04/1989	Seiferth	219	10.55 E	
m	4,865,921	09/1989	Hollenberg et al.	428	461	
re	4,883,936	11/1989	Maynard et al.	219	10.55 F	
he	4,943,456	07/1990	Pollart et al.	428	34.3	
rè	5,077,455	12/1991	Peleg et al.	219	10.55 E	
re	5,180,894	01/1993	Quick et al.	219	10.55 E	
re	5,217,768	06/1993	Walters et al.	428	35.8	
re	5,230,914	07/1993	Akervik	426	107	
re	5,260,536	11/1993	Peery	219	10.55 E	
M	5,317,118	05/1994	Brandberg et al.	219	727	
re	RE. 34,683	08/1994	Maynard et al.	219	703	
ne	5,338,921	08/1994	Maheux et al.	219	730	
ve	5,630,959	05/1997	Owens	219	730	
re	6,093,920	07/2000	Beckwith	219	734	
re	6,133,560	10/2000	Zeng et al.	219	730	
M	6,204,492 B1	03/2001	Zeng et al.	219	728	
re	6,303,913 B1	10/2001	Bono et al.	219	730	
ne	6,414,290 B1	07/2002	Cole et al.	219	759	

## FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

	DOCUMENT	PUBLISHED				TRANSL	ATION
1	NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
N	WO 91/07861	05/1991	PCT				

		C	THER DOCU	MENTS (Including Author, 1	litle, Date, Pertinent Pages, Etc.)	
EXAMINE	ו ו ואוני		H.	LEUNG	DATE CONSIDERED	5-27-2005
EXAMINE	R: Initial if	citation conside	ered, whether o	or not citation is in conforman	ce with MPEP 609; Draw line the	rough citation if not in conformance

EXAMINER: Initial it citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation it not in conformance and not considered. Include copy of this form with next communication to applicant.